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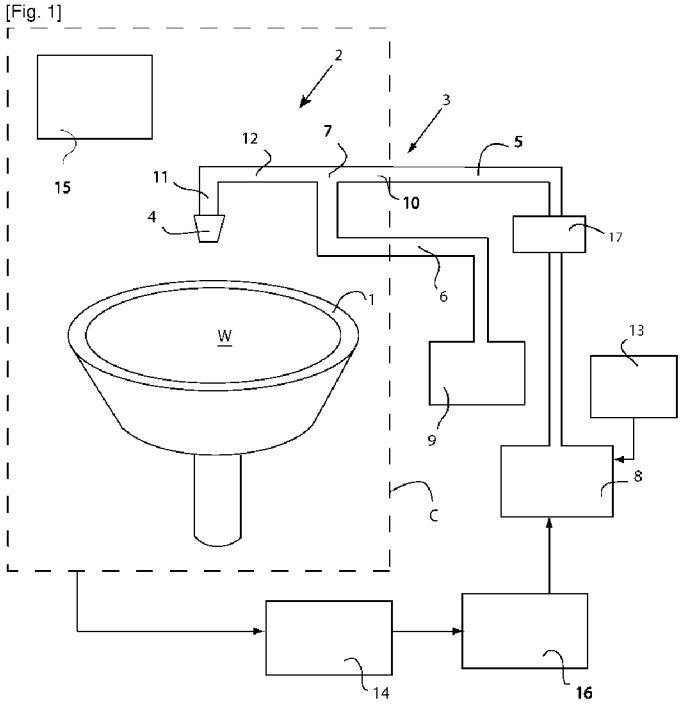
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Declarations under Rule 4.17:

[Continued on next page]

(54) **Title**: METHOD AND APPARATUS FOR SURFACE TREATMENT USING A MIXTURE OF ACID AND OXIDIZING GAS

[Fig. 1]



(57) **Abstract**: Improved removal of ion-implanted photoresist in a single wafer front-end wet processing station is achieved by combining gaseous ozone and heated sulfuric acid such that a gas/liquid dispersion or foam of ozone in sulfuric acid is applied in a layer to the wafer surface to be treated.

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— *as to applicant's entitlement to apply for and be granted a patent (Rule 4.17(ii))*

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